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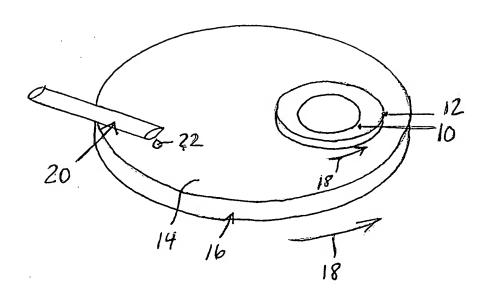


Figure 1

using a control system to detect
harmonic oscillation
or noise associated therewith

changing at least one characteristic of the chemical mechanical polishing process to reduce the harmonic oscillation, or generating an audio signal to counter the noise associated with the harmonic oscillation

26

Figure 2

a detector configured to detect either harmonic oscillation or noise associated therewith

28

a reactor configured to receive information from the detector and react by at least one of: changing at least one characteristic of the chemical mechanical polishing process to reduce the harmonic oscillation, and generating an audio signal to counter the noise associated with the harmonic oscillation

30

Figure 3

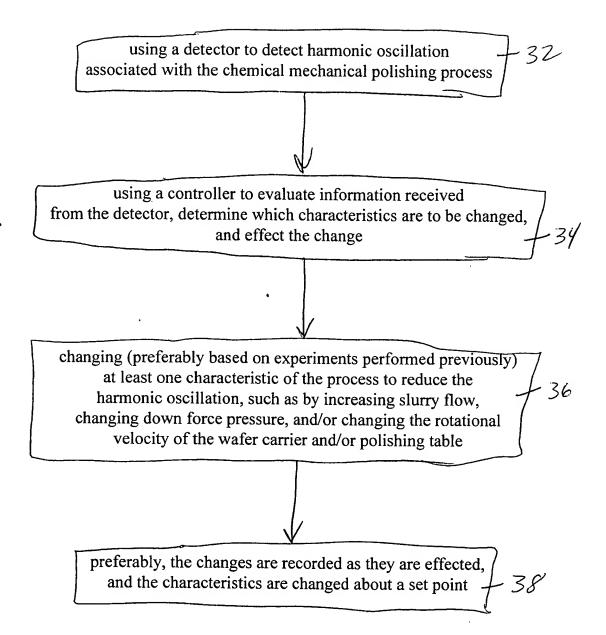


Figure 4

a detector configured to detect
harmonic oscillation associated
with the chemical mechanical polishing process

a controller configured to evaluate information received from the detector and change at least one characteristic of the chemical mechanical polishing process to reduce the harmonic oscillation which has been detected, such as by increasing slurry flow, changing down force pressure, and/or changing the rotational velocity of the wafer carrier and/or polishing table

Figure 5

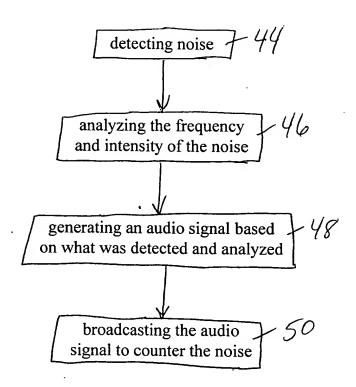


Figure 6

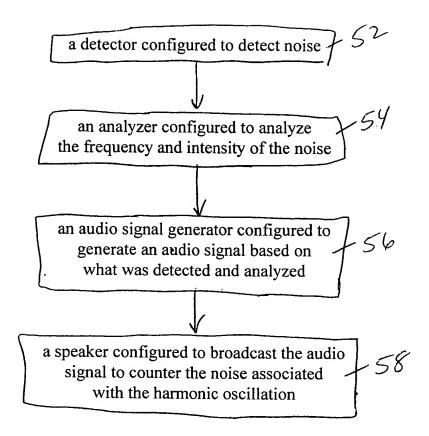


Figure 7

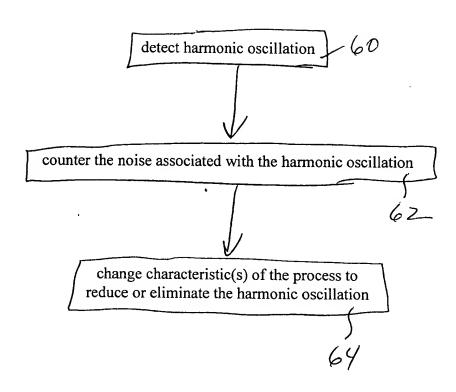


Figure 8

a detector configured to detect harmonic oscillation

a reactor configured to counter the noise associated with the harmonic oscillation and change one or more characteristics of the chemical mechanical polishing process to reduce or eliminate the harmonic oscillation

68

Figure 9

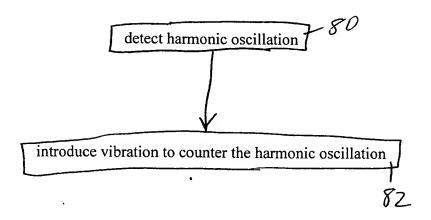


Figure 10

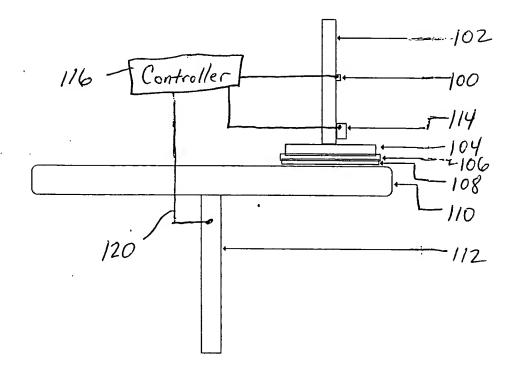


Figure 11